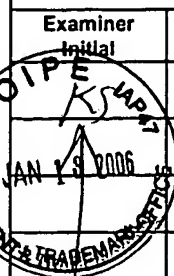


PTO-1449 INFORMATION DISCLOSURE STATEMENT BY APPLICANT <u>LIST OF ITEMS</u> (Use several sheets if necessary)	Attorney's Docket Number JEN-0111-P	Serial Number 10/665,391
	Name of Applicant Shuhua Jin et al	
	Filing Date 09/19/2003	Group 1714

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	NAME	Class	Subclass	Filing Date if Appropriate
	3 066 112	11/27/1962	Bowen			
	3 179 623	04/20/1965	Bowen			
	3 194 784	07/13/1965	Bowen			
	3 751 399	08/07/1973	Lee et al			
	3 755 420	08/28/1973	Stoffey et al			
	3 926 906	12/16/1975	Lee II et al			
	4 306 913	12/22/1981	Mabie et al			
	4 544 359	10/01/1985	Waknine			
	4 547 531	10/15/1985	Waknine			
	4 764 497	08/16/1988	Yuasa et al			
	5 276 068	01/04/1994	Waknine			
	5 444 104	08/22/1995	Waknine			
	5 876 210	03/02/1999	Klee et al			
	5 936 006	08/10/1999	Rheinberger et al			
	5 969 000	10/19/1999	Yang et al			
	6 013 694	01/11/2000	Jia et al			
6 362 251 B1	03/26/2002	Alkemper et al				
6 387 981 B1	05/14/2002	Zhang et al				
6 417 246 B1	07/09/2002	Jia et al				

OTHER INFORMATION (including author, title, date, pertinent)

	Lichtenhan, Joseph D., "Polyhedral Oligomeric Silsesquioxanes: Building Blocks for Silsesquioxane-Based Polymers and Hybrid Materials", Comments Inorg. Chem. (1995), Vol. 17, No. 2, pp. 115-130
	Lichtenhan, Joseph D., et al, "Linear Hybrid Polymer Building Blocks: Methacrylate-Functionalized Polyhedral Oligomeric Silsesquioxane Monomers and Polymers", Macromolecules (1995) Vol. 28, pp. 8435-8437
	NASA High-Performance POSS-Modified Polymeric Composites, NASA Tech Briefs, February 2001, p. 52
	Feher, Frank J., et al, "Silsesquioxanes As Models For Silica Surfaces", American Chemical Society, 1989, Vol. 111, pp. 1741-1748

EXAMINER <i>Shuhua Jin</i>	DATE CONSIDERED 2/06
--------------------------------------	--------------------------------

* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.